

References

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List of Figures

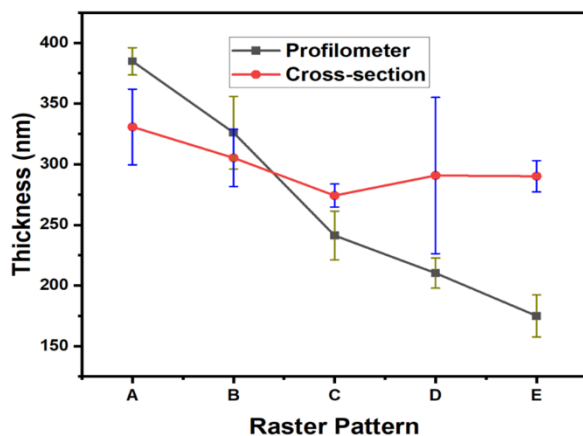


Figure 1. Plot comparing the overall film thickness for different raster patterns (A-E) as measured by profilometry (black squares, average of 4 measurements across substrate) and cross-sectional SEM (red circles, average of 5 measurements across the cleavage).

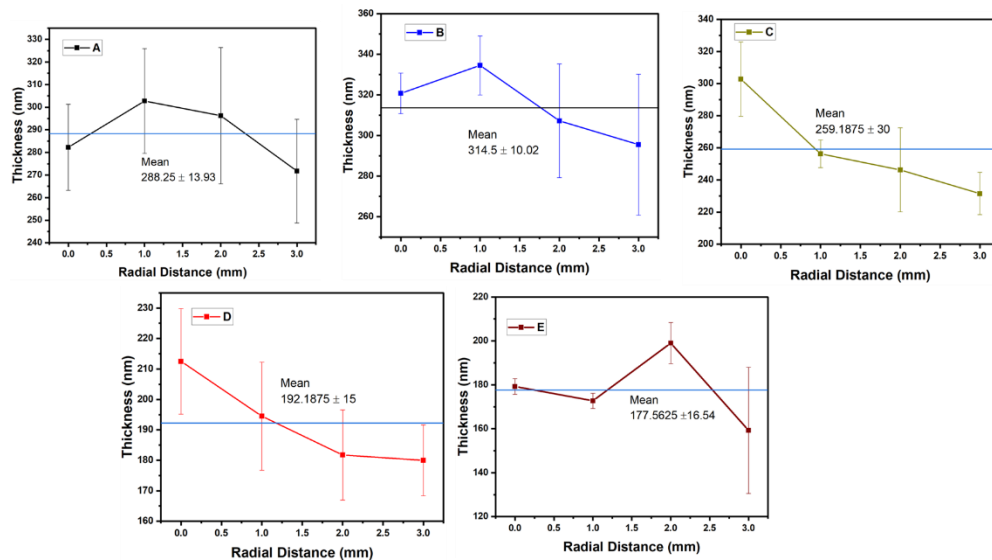


Figure 2. Spatial uniformity measurement for A-E raster patterns. Thickness measurements by profilometer vs radial distance from center to the substrate edge, with measurements taken at 1 mm intervals. Film thickness shows both intra-pattern variation across individual films and inter-pattern differences among the various laser raster patterns. The horizontal line represents the mean film thickness of each pattern of the plotted graph. Pattern B shows the thickest film and with the most uniform profile, showing a standard deviation of ~10 nm. However, pattern C demonstrates the largest thickness variation with a standard deviation of 30 nm.